

L Number	Hits	Search Text	DB	Time stamp
-	119	257/625.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT;	2002/12/13 12:38
-	113	257/625.ccls. and (@ad<20010501)	US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT;	2002/12/13 12:48
-	191	438/740.ccls. and (@ad<20010501)	US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT;	2002/12/13 12:49
-	115	(438/740.ccls. and (@ad<20010501)) and wafer	US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT;	2002/12/13 12:52
-	59	257/459.ccls. and (tan or wn or tasn or sin or tungsten or tantalum or (etch adj stop))	US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT;	2002/12/13 13:17
-	174	438/459.ccls. and (tan or wn or tasn or sin or tungsten or tantalum or (etch adj stop))	US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT;	2002/12/13 14:02
-	3135	(wafer or (semiconductor adj substrate)) near (trench or cavity or recess)	US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT;	2002/12/13 14:01
-	5503	(wafer or (semiconductor adj substrate)) near (via or trench or cavity or recess)	US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT;	2002/12/13 14:01
-	5	(plastic adj mold) near epoxy	US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT;	2002/12/13 14:16
-	36	((wafer or (semiconductor adj substrate)) near (via or trench or cavity or recess)) and ((trench or cavity or recess or via) near (tan or wn or tasn or sin or tungsten or tantalum or (etch adj stop)))	US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT;	2002/12/13 14:22